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INFORMATION DISC STATEMENT BY APP			
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	INFORMATION DISCLOSURE STATEMENT BY APPLICANT		
	(Use several sheets if necessary)		
		Applicant:	
		Kouvetakis, et al.	
		Filing Date:	Group:
		December 8, 2005	2812

COMMONLY OWNED CO-PENDING APPLICATIONS

Examiner		
Initial		
R5P	1.	Kouvetakis, et al., U.S. Patent Application No. 10/559,980, Filed on December 8, 2005.
RJP	2.	Kouvetakis, et al., U.S. Patent Application No. 10/559,979, Filed on December 8, 2005.

EXAMINER 7	- Outs	DATE CONSIDERED 4/19/07